

IN THE ABSTRACT OF THE DISCLOSURE:

Please amend the abstract to read as follows:

ABSTRACT OF THE DISCLOSURE

~~The object of the present invention is to provide a~~ A pattern inspecting technique ~~that can reduce~~, depending on the kind of materials, can reduce damage including shrinkage to materials when the materials are prone to such damage as shrinkage and spoilage caused by electron beam irradiation. ~~A method according to the present invention comprises a step of~~ This is accomplished by scanning a sample of ~~a semiconductor device or the like~~ with a primary electron beam, ~~a step of~~ detecting secondary electrons generated₁ or electrons reflected from the semiconductor device₁ or both the former and latter electrons₁ and converting the electrons into signals, and ~~a step of~~ transforming the signals into an image, displaying the image, and detecting defective spots in the circuit pattern of the ~~semiconductor device~~ sample. ~~In the method and apparatus of the present invention,~~ The irradiation density (dose per unit area) of the electron beam is monitored and limited depending on the kind of material of the circuit pattern under inspection and the inspecting conditions, and damage₁ such as shrinkage and spoilage to the materials during electron beam irradiation₁ is reduced to an allowable range.